

Dicing Tape behavior within a Plasma Dicing Environment

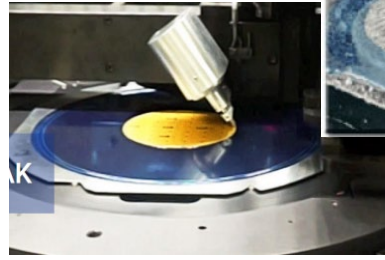


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IMAPS DPC 4th – 7th March 2019, Arizona

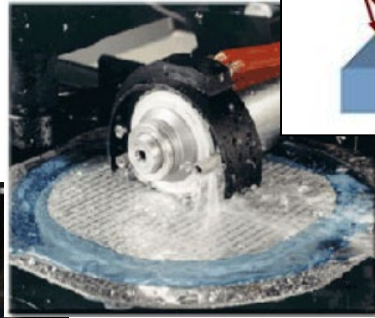


Plasma Dicing-The next step in evolution of die singulation

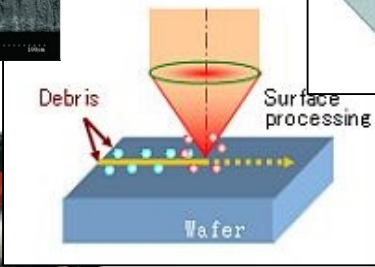
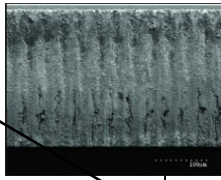
Conventional Dicing Techniques



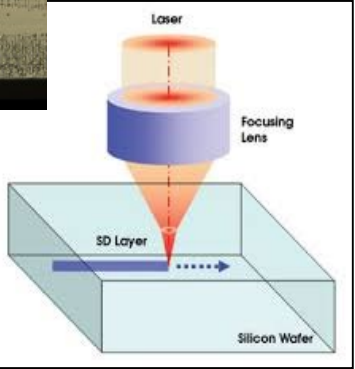
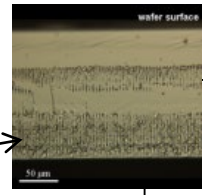
Cleaving



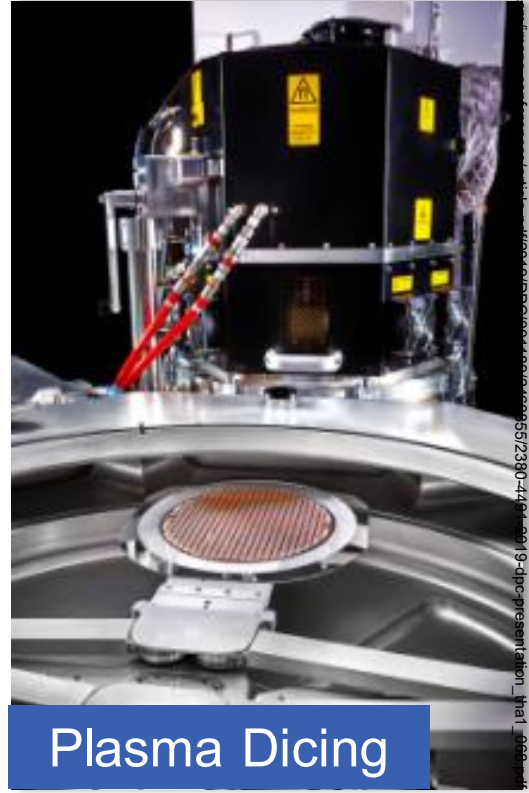
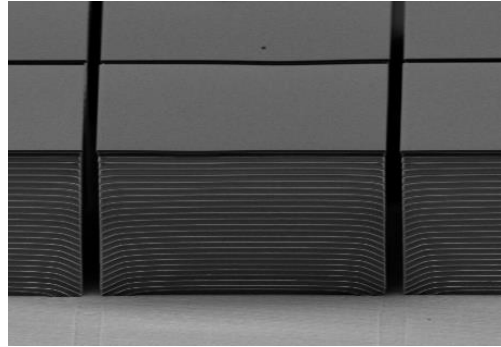
Blade



Laser Ablation



Stealth

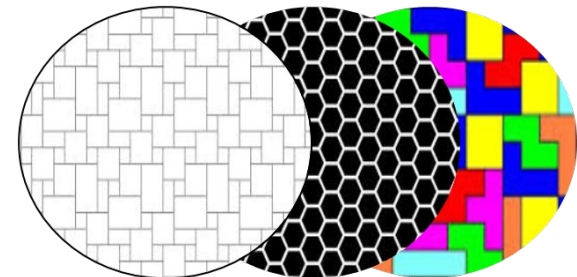
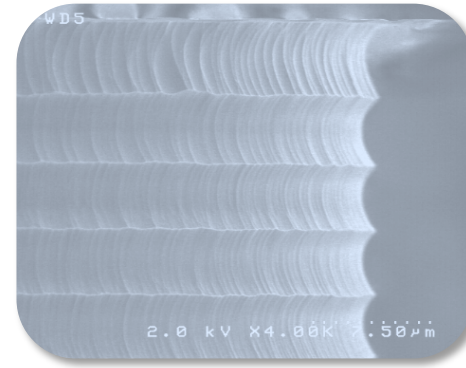


Plasma Dicing



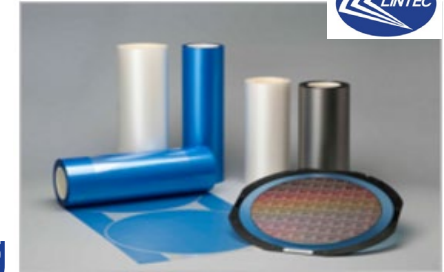
The Benefits of Dicing with Plasma

- Limited Damage
 - Bosch etch creates clean scallops
 - No vibrations, debris, water
 - Increased die strength
 - Yield improvement
- Die Density
 - Narrower dicing lanes
 - Die shape/location can be varied
- Throughput
 - Parallel process
 - Largely independent of die size
 - Cluster approach for higher output/floor area



Dicing tape

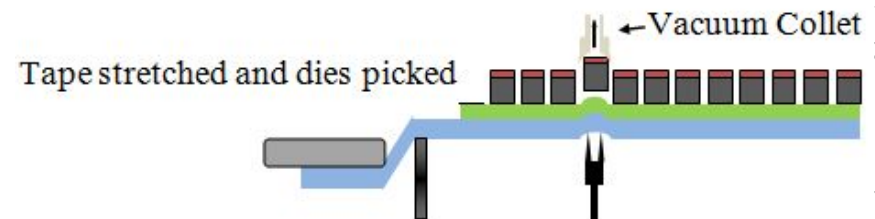
- Properties of tapes have been designed for traditional dicing techniques
 - The mechanical stresses of saw dicing
 - Thermal challenges of full cut laser dicing
 - The UV transparency for back-side stealth dicing
- Tape performance needs to be characterised for plasma dicing to ensure successful damage free die pick-up



Can we use standard
dicing tapes for
Plasma Dicing?

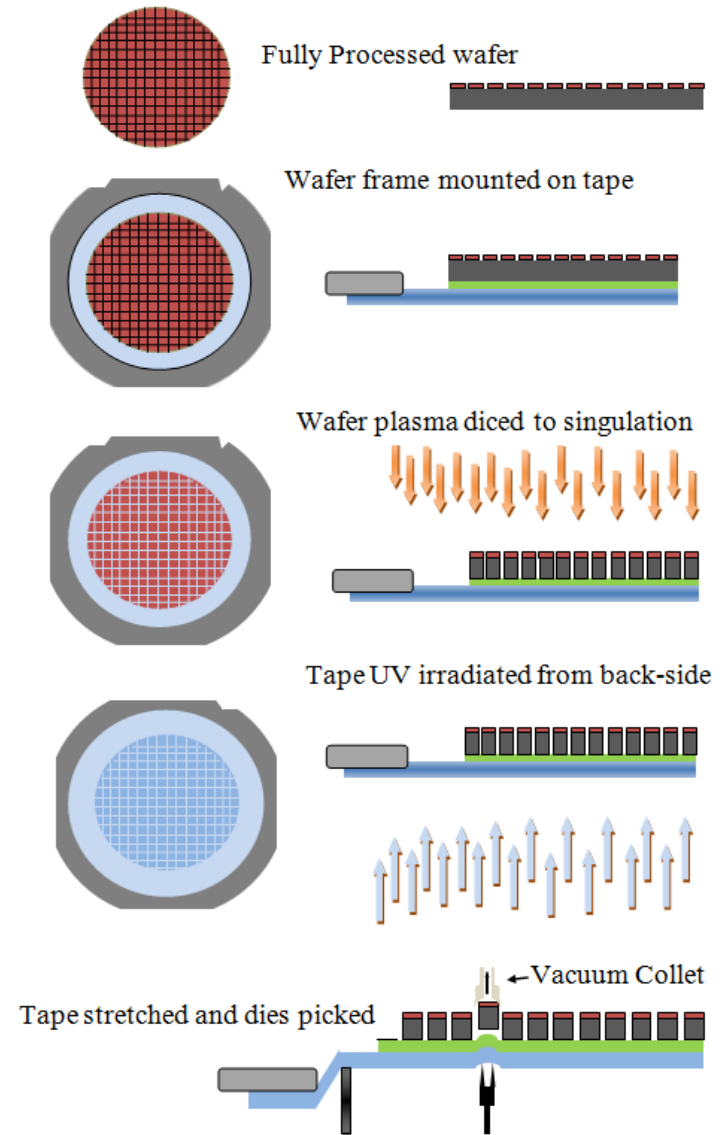
Dicing tape tests

- Out-gassing and thermal performance of tape
- Elongation and tensile strength measurement
- Plasma exposure and adhesive curing (SF₆ & O₂ plasma)
- Die pick-up force measurement (saw diced versus plasma diced die)



Dicing tape

Typical use of tape during dicing and die pick-up

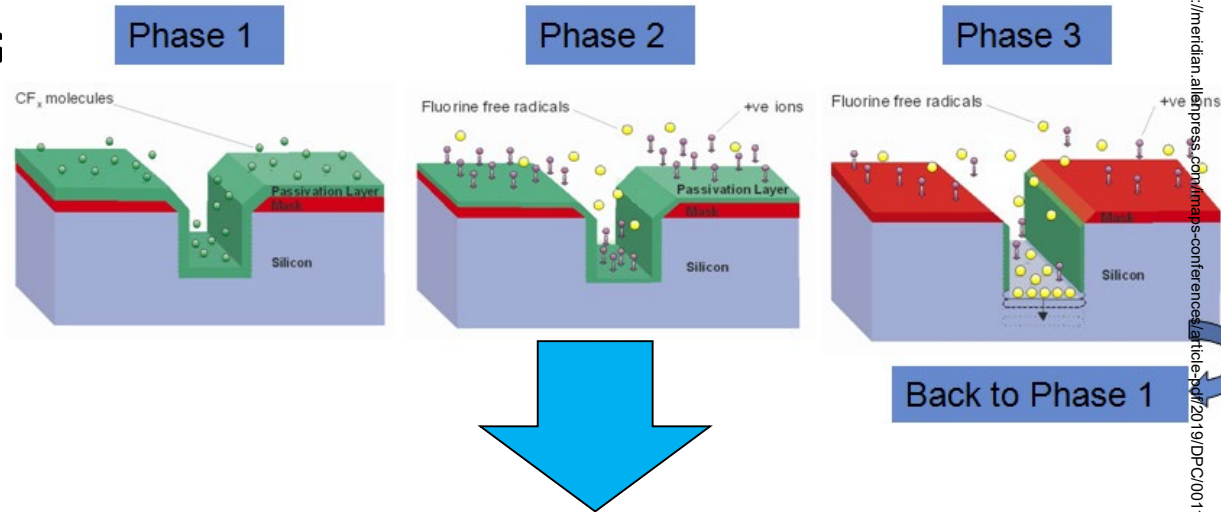


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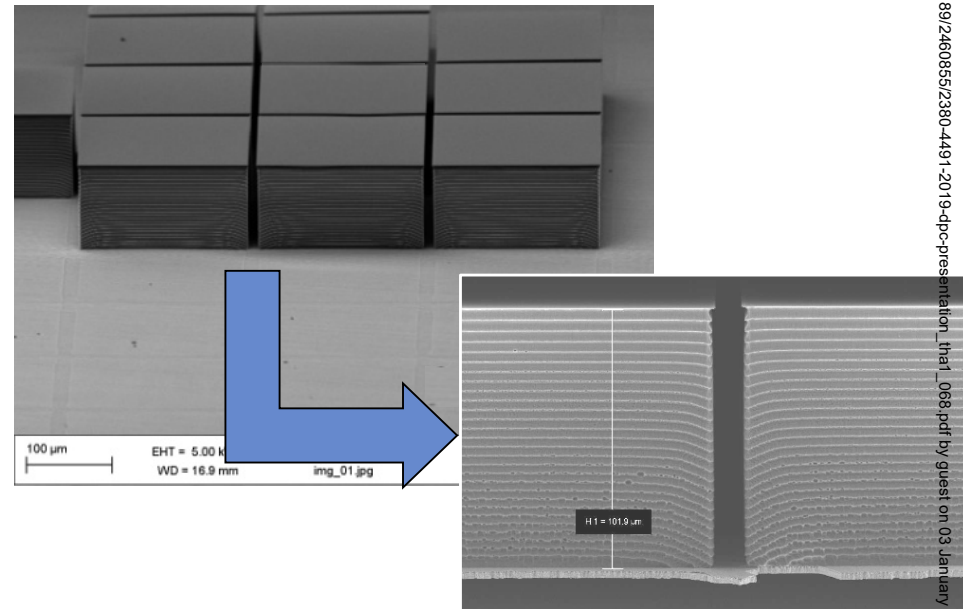
What is plasma dicing?

The "Bosch" Process

- Si etch process
 - Repeating loops
- Phase 1 Polymer dep
Phase 2 Polymer removal
Phase 3 Isotropic Si etch



A time multiplexed deep anisotropic etching technique used in high volume manufacture for Deep Silicon Etching Applications e.g. MEMS, TSV, etc

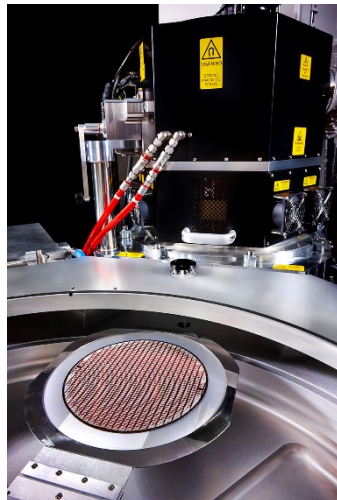


Dicing tape performance in a plasma

- Dicing tape tests were performed using a Rapier S Plasma dicing module
 - Tests were performed on PO (Polyolefin) & PVC (Polyvinylchloride) tapes of varying adhesive strengths

A dual source plasma reactor designed for high silicon etch rate with low cross wafer non-uniformity

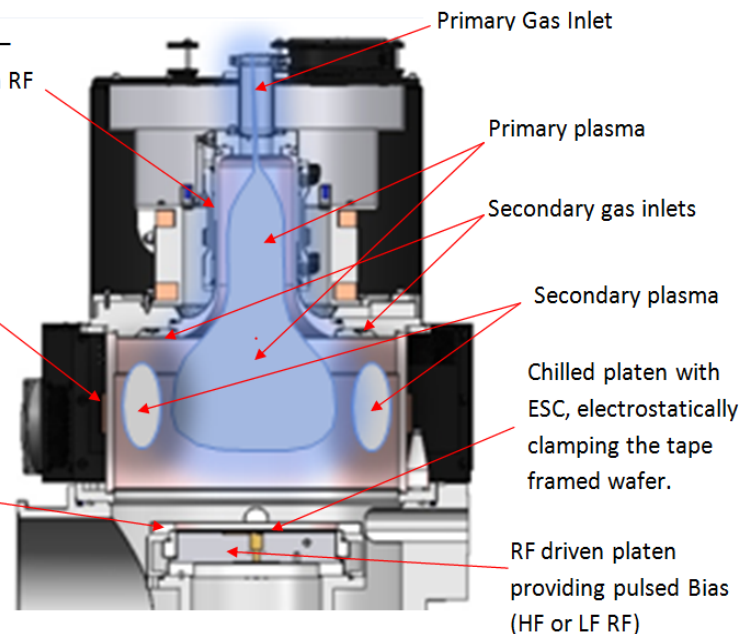
Rapier S Plasma Dicing Process Module



Primary (DSi) source –
Bell jar chamber with RF
at 13.56MHz

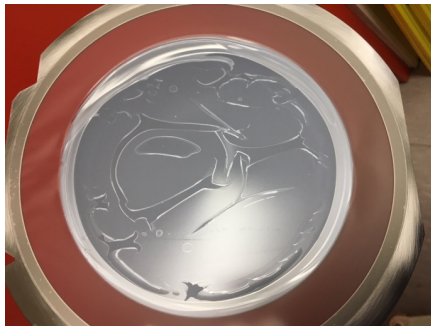
Secondary (ICP)
source – Ceramic
chamber with RF at
13.56MHz

Frame Cover Ring
used to protect the
frame from plasma
exposure.

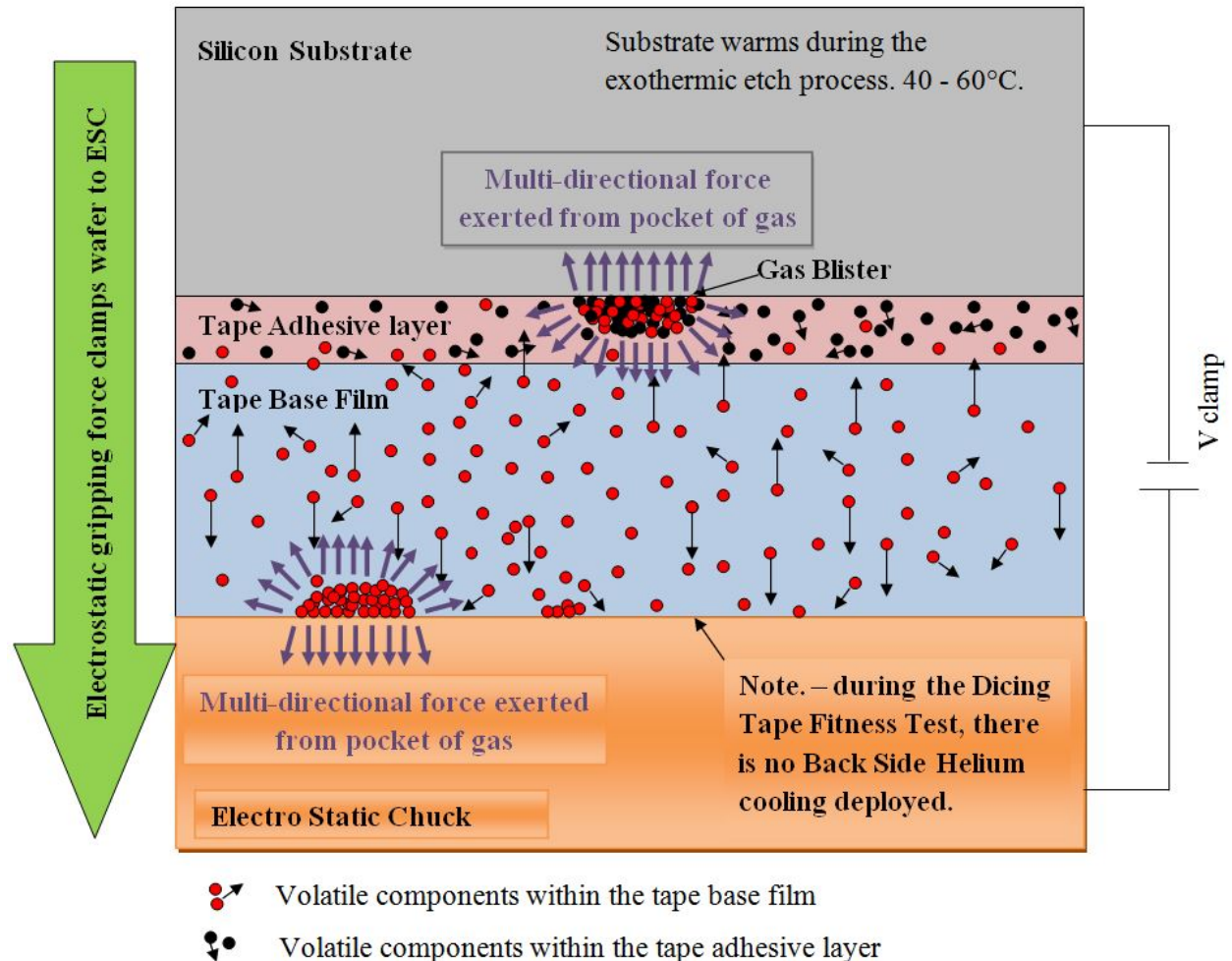
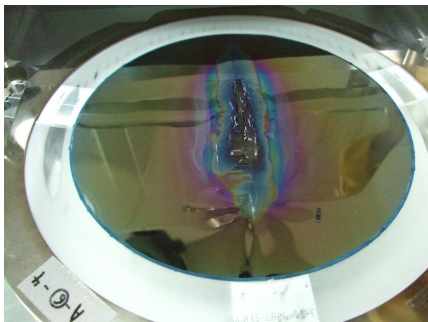


Tape outgassing & thermal performance

What happens when tape out-gasses and why is it important?



Tape out-gassing can cause gas blister underneath thinned wafer causing declamp or substrate damage



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Tape performance results

- Polyolefin tapes with low to medium adhesive strength and thinner base film demonstrated best results

Tape ID	Base Film	UV or non-UV	Adhesive classification	Base & Adhesive thickness [um]	Adhesive Strength (before/after UV) [mN/25mm]	Average Score	Risk of declamp
PO10	PO	UV	Type B	80/5	4900/80	19.0	Very low
PO9	PO	UV	Type B	80/5	2800/160	19.0	Very low
PO8	PO	UV	Type A	80/10	4100/120	17.5	Low
PO7	PO	UV	Type B	80/10	1960/200	17.4	Low
PO6	PO	non-UV	Type B	80/5	800/800	17.4	Low
PET1	PET	UV	Type A	25/10	13800/220	17.4	Low
PO5	PO	non-UV	Type B	80/10	880/880	16.4	Low
PO11	PO	UV	Type B	110/100	8580/30	16.0	Medium
PO4	PO	UV	Type B	80/5	4400/100	15.6	Medium
PO2	PO	UV	Type A	80/15	12300/690	13.0	Medium
PO3	PO	UV	Type A	80/5	8400/750	12.8	Medium
PO1	PO-ESD	UV	Type B	80/5	4700/100	7.8	Medium
PVC3	PVC-DEHP-ESD	UV	Type A	80/10	3300/320	4.8	High
PVC2	PVC-other	UV	Type A	80/10	3300/320	3.0	High
PVC1	PVC-DEHP	UV	Type A	80/10	2800/290	2.7	High

Note ! The out-gassing & thermal performance test uses a highly aggressive etch to allow differentiation between tapes.

Tape elongation and tensile strength

- Elongation & tensile strength was measured after exposure to different plasma or non-plasma environments
 - Heat
 - Vacuum
 - Individual gas plasma
 - Partial plasma dicing process
- Tapes Used:
 - LINTEC UV Tapes PO2 & PO10
 - LINTEC UV Tape PVC1

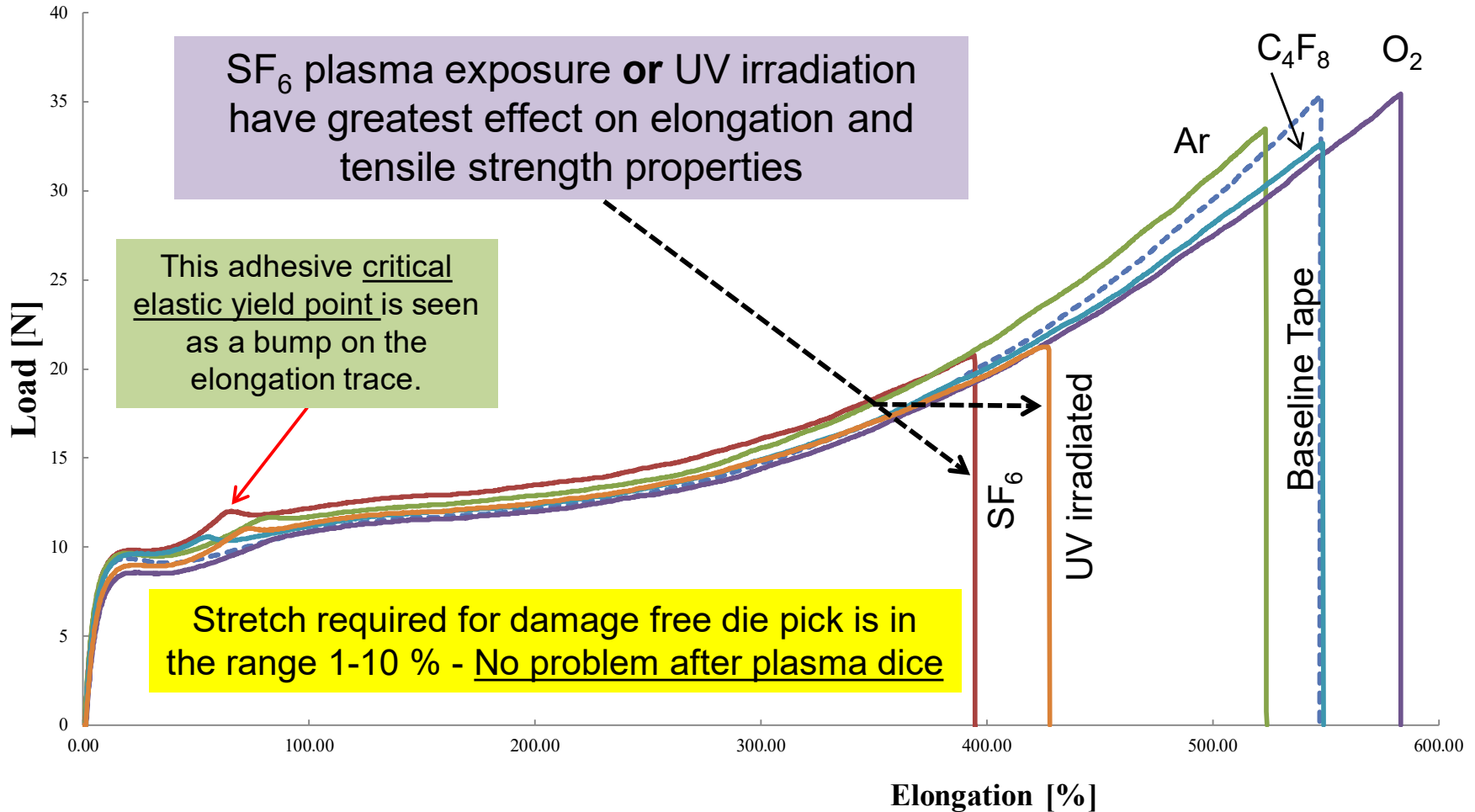


Tape stretched during elongation and tensile strength tests

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Tape elongation and tensile strength

Tape PO10 - CD Elongation curve on Baseline Tape versus exposure to different plasma species



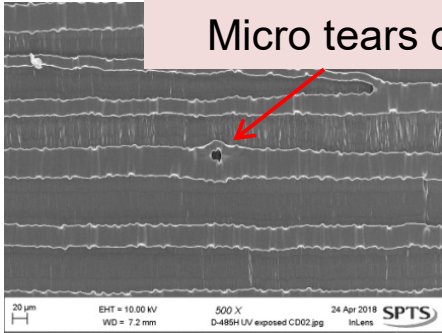
SF₆ plasma exposure or UV irradiation have greatest effect on elongation and tensile strength properties

This adhesive critical elastic yield point is seen as a bump on the elongation trace.

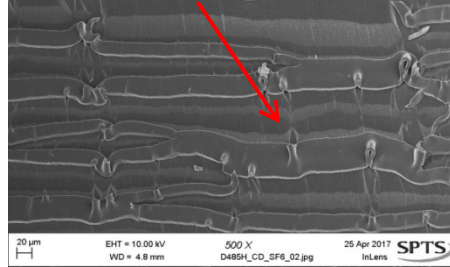
Stretch required for damage free die pick is in the range 1-10 % - No problem after plasma dice

Tape elongation and tensile strength

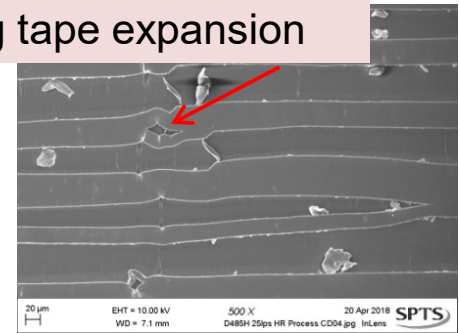
Micro tears caused by firmly attached adhesive limiting tape expansion



UV irradiation

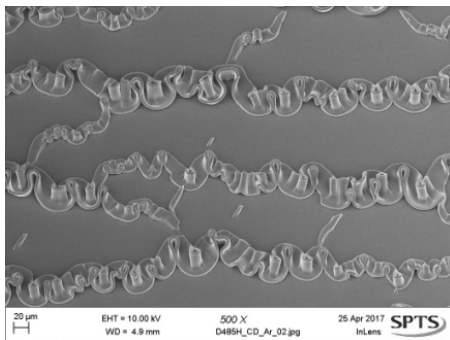


SF₆ Plasma

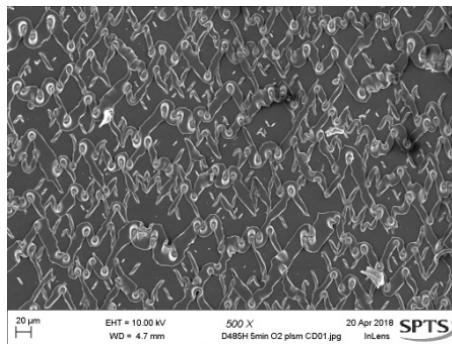


Dicing Plasma

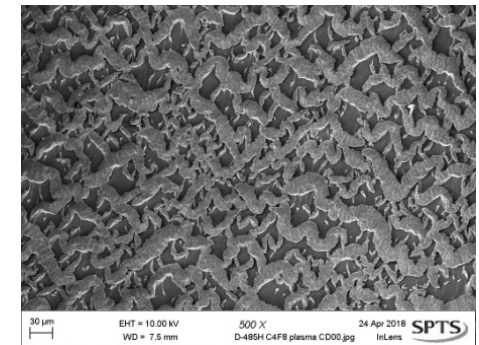
Similar looking SEM images for samples UV irradiated or exposed to SF₆ or dicing plasma



Ar Plasma



O₂ Plasma

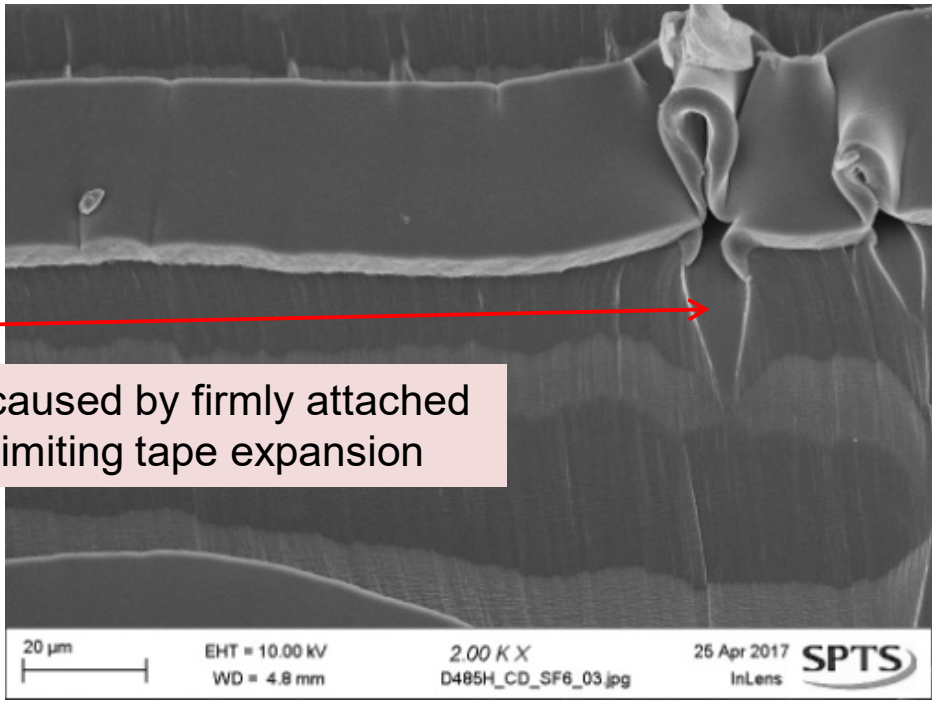
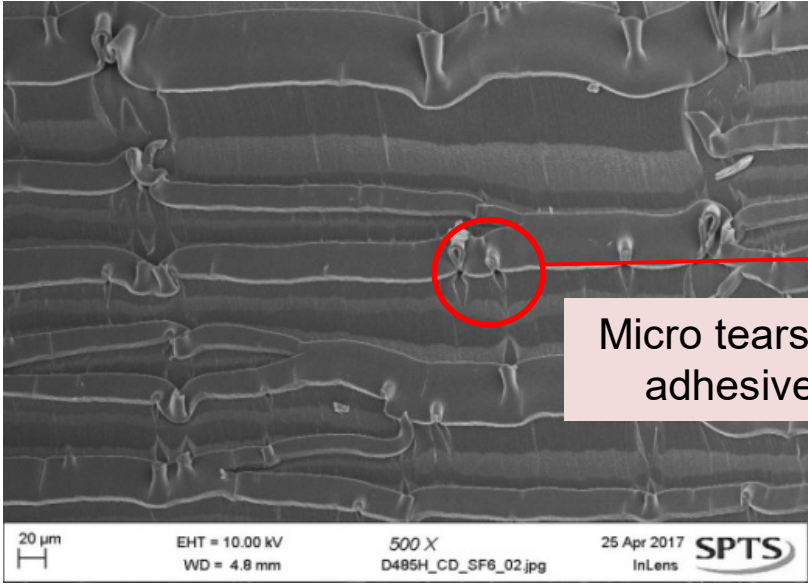


C₄F₈ Plasma

Similar looking SEM images for samples exposed to Ar, O₂ and C₄F₈ plasma

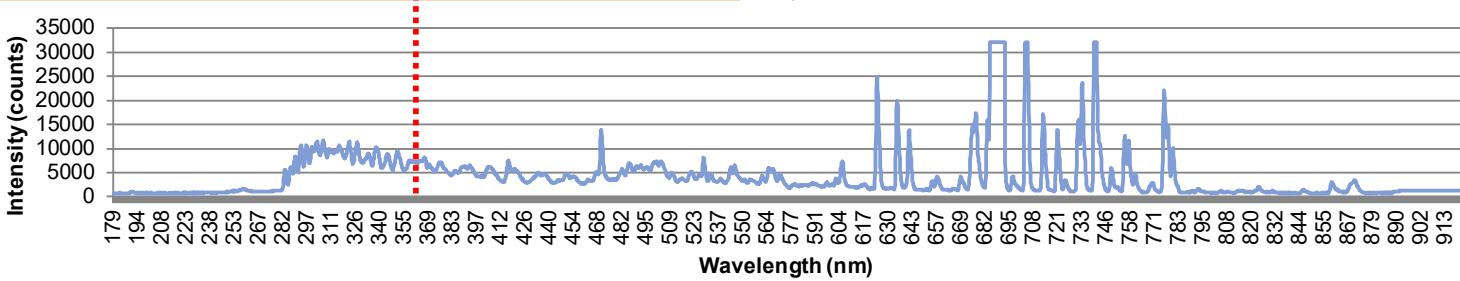
Tape elongation and tensile strength

UV sensitive Adhesive cured from UV wavelengths within SF₆ plasma spectra



Micro tears caused by firmly attached adhesive limiting tape expansion

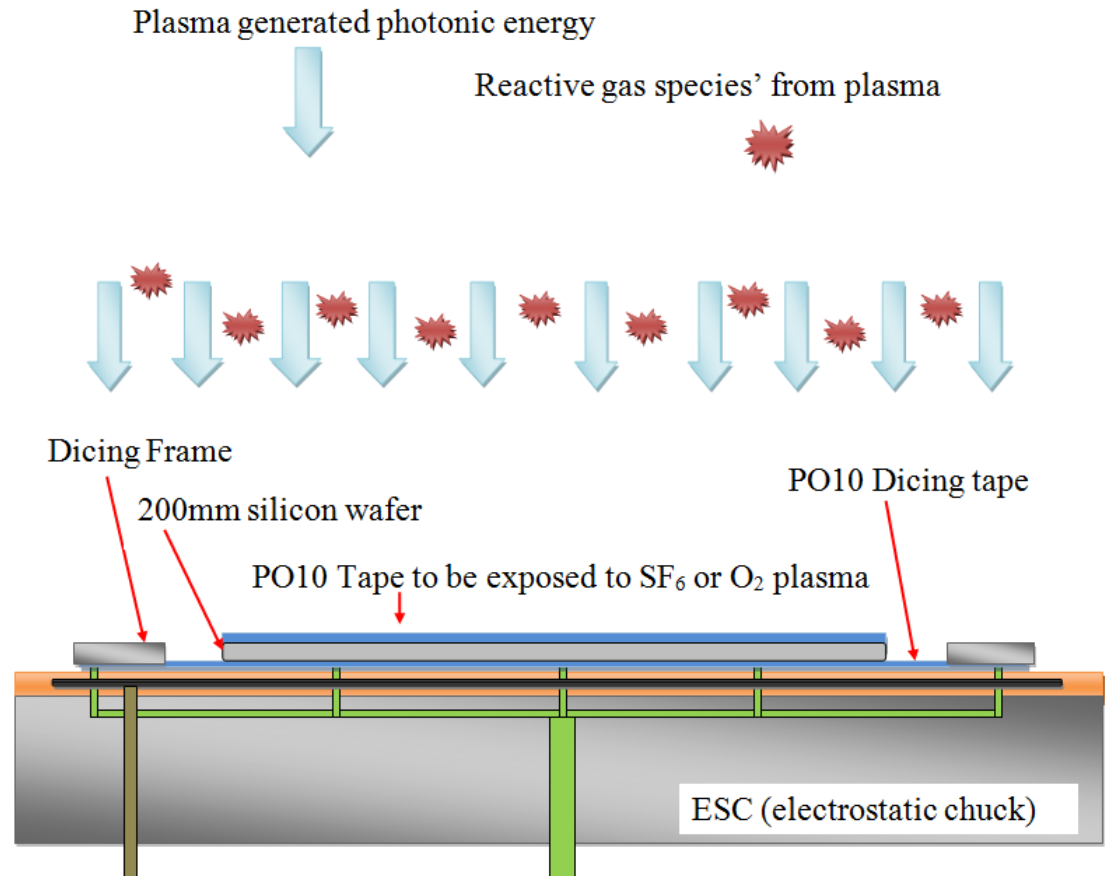
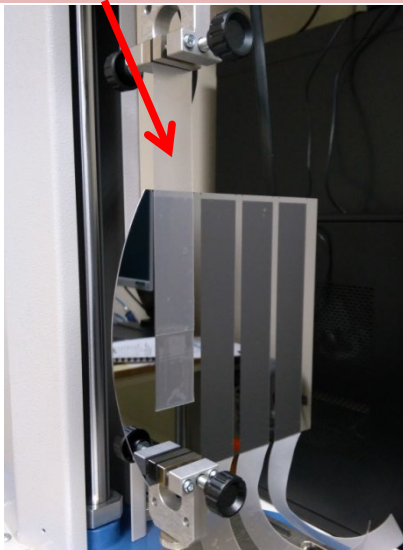
Wavelength of UV recommended for adhesion release is around 365nm



Plasma exposure and adhesive curing

- Further investigation into a link between plasma exposure and the adhesive curing process
 - SF₆ plasma and O₂ plasma

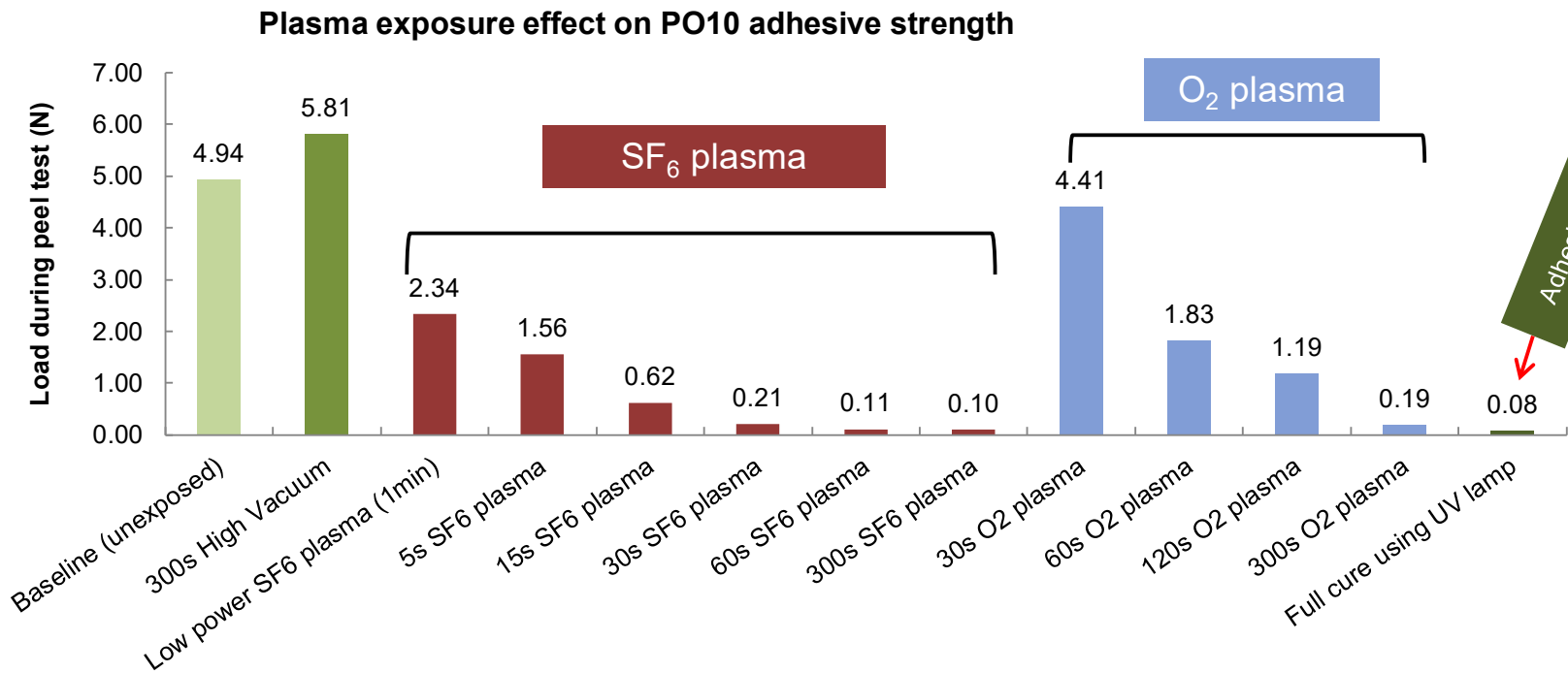
Adhesive Peel Strength measurement after plasma exposure



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Plasma exposure and adhesive curing

- Plasma exposure can trigger the adhesive curing process
- Curing rate dependent on plasma species & exposure time



Adhesion strength minimised

SF₆ plasma exposure cures UV adhesive faster than O₂ plasma
60s SF₆ plasma – 99% cured 60s O₂ plasma only 60% cured

Die Pick-Up Force Measurement (plasma dicing v saw dicing)

- 10x10mm die size
 - Plasma diced @ SPTS (dicing kerf widths of 10, 20 and 40 μ m).
 - Saw diced @ LINTEC Corporation Research Centre in Japan
40 μ m kerf widths
- Tapes
 - UV tapes PO2 - soft adhesive P010 – hard adhesive

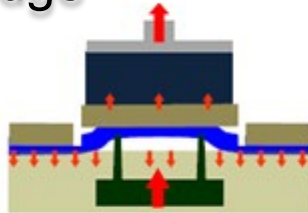
Die Pick-Up Force Measurement

Tape expanded 5mm
Vacuum collet grips top side of die

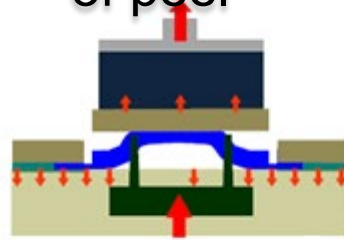


Needle set pushed upward to
separate die from tape

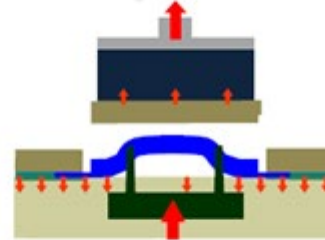
Peeling at
chip edge



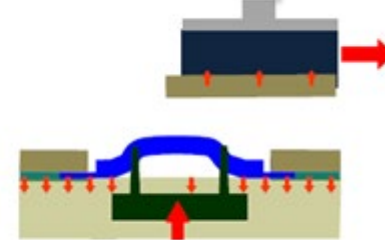
Propagation
of peel



Peel end &
successful
peel-off



Collet with chip
transfers for
packaging



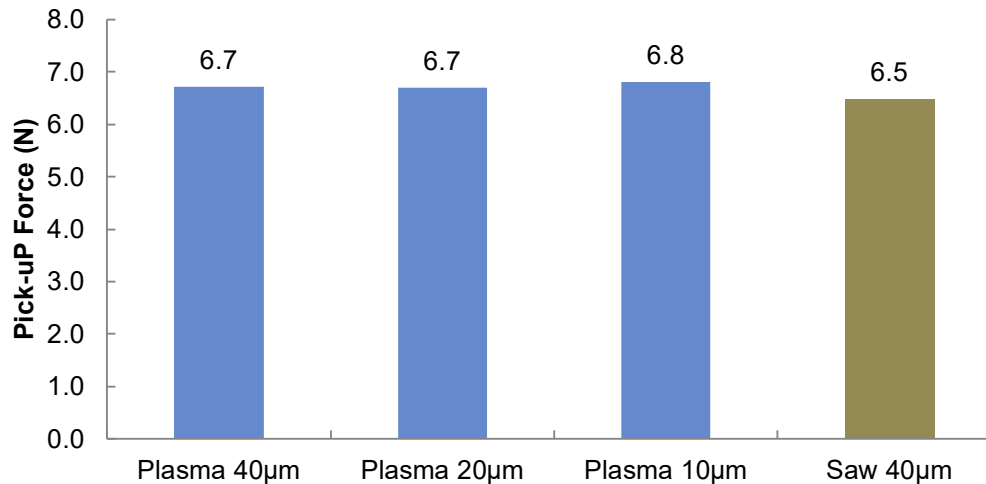
Needle load (N) is related to the pick-up force
required for successful die separation from tape

LINTEC journal paper – N. Saiki, K. Inaba, K. Kishimoto, H. Seno, and K. Ebe, "Study on peeling behaviour in pick-up process of IC chip with adhesive tapes," *Journal of Solid Mechanics and Materials Engineering*, vol. 4, no. 7, pp. 1051-1060, 2010

Die Pick-Up Force Measurement - Results

- PO10 tape (hard adhesive)
 - Pick-up force on plasma diced dies comparable with saw diced dies

10x10mm Die Pick-Up Force measurements from PO10
Plasma dicing versus saw diced wafers



- PO2 tape (soft adhesive)
 - Pick-up force measurement on plasma diced & saw diced samples not possible
 - Post UV adhesive strength not designed for 10x10mm devices

Conclusion

- Adhesive curing is triggered by plasma exposure
 - Limited to dicing lane area at singulation
 - No detrimental effect at die pick-up
 - Plasma dicing has minimal effects on tape elongation and tensile strength – no problem during tape stretch
- Selection of tape should be tailored for die size, die thickness & plasma dicing etch rate

Can we use standard
dicing tapes for
Plasma Dicing?

YES